

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Cyril Cabral, Jr., et al.

Docket: YOR920030218US1 (16714)

Serial No:

10/662,900

Date:

July 26, 2004

Filed:

September 15, 2003

REDUCTION OF SILICIDE FORMATION TEMPERATURE ON SiGe CONTAINING For:

SUBSTRATES

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

REQUEST FOR CHANGE OF MAILING ADDRESS

Sir:

Applicant(s) request(s) that all future correspondence in connection with this application be directed and addressed to:

> STEVEN FISCHMAN, ESQ. SCULLY, SCOTT, MURPHY AND PRESSER Correspondence Address Customer No. 23389 Direct all telephone calls to: (516) 742-4343.

> > Respectfully submitted:

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